

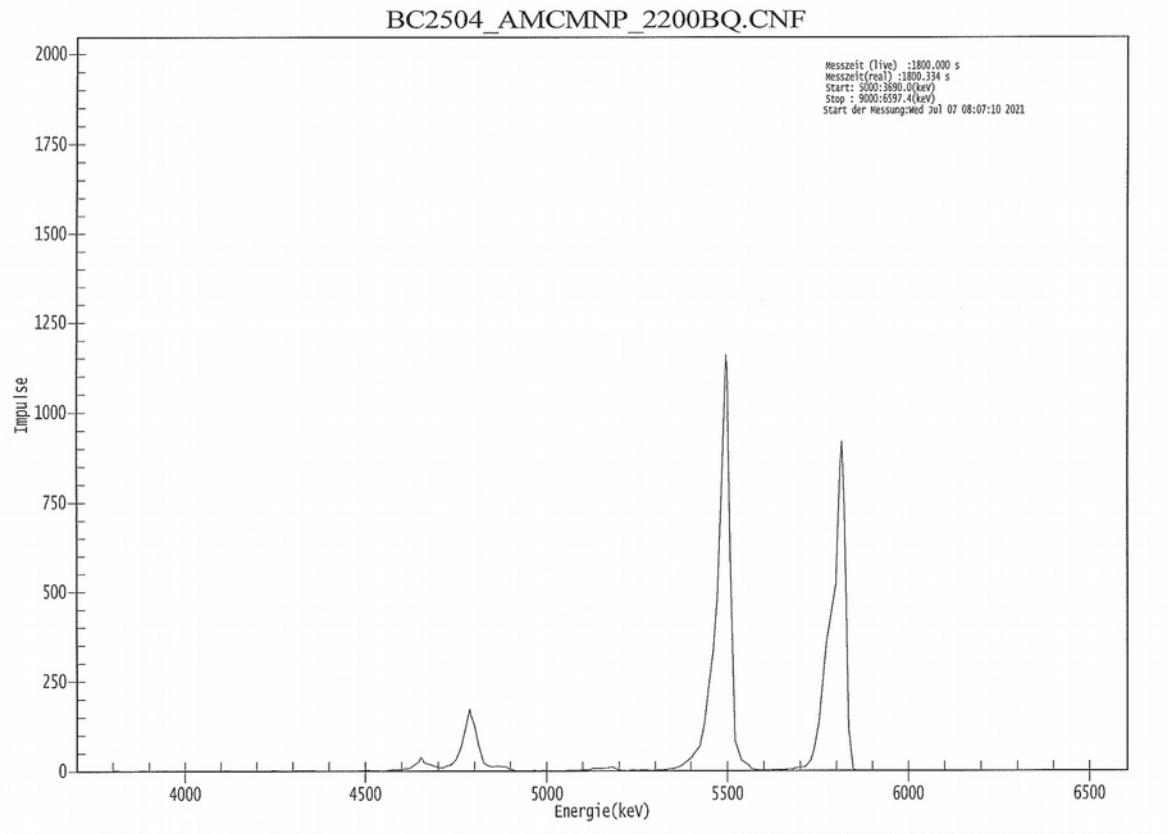
Measurements with alpha source

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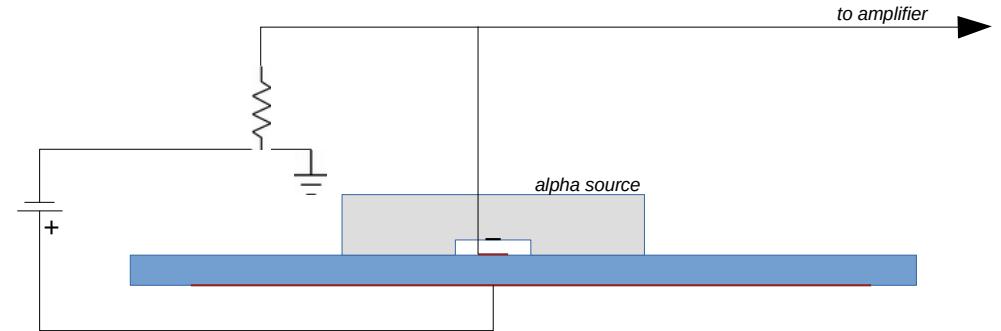
Alpha source

- ^{241}Am (1000 Bq)
 - 5.486 MeV (85%)
 - 5.443 MeV (13%)
 - 5.388 MeV (2%)
- ^{244}Cm (1000 Bq)
 - 5.765 MeV (23%)
 - 5.806 MeV (77%)
- ^{237}Np (200 Bq)
 - 4766 MeV (9%)
 - 4771 MeV (23%)
 - 4788 MeV (48%)
- Tolerance on activity: +/- 30%
- Active diameter: 7 mm



Setup

- Sapphire
 - 110 um (Wuppertal)
 - 150 um (US company)
- low noise HV power supply
- new home-made charge amplifier calibrated to 245 mV/fC
RMS noise $\sim 12 \text{ mV} \sim 0.05 \text{ fC} \sim 780 \text{ e}^-$



Working parameters

- HV up to 1200 V
- 6.5 mm nominal air gap from source to sapphire
7 mm used for calculations to keep into account also the ~100 nm of Ti-Ag deposition
- Estimated Alfa kinetic energy and ionization charge produced

Average initial kinetic energy		Range in sapphire		Charge created
initial	at surface	direction normal to surface		
MeV	MeV	um		fC
5.638	4.985	10.900		29.540

Simple model

- In a setup with uniform electric field inside the sapphire, with:

τ electrons lifetime
 μ electron mobility

d sapphire thickness

V electric field potential

v_d drift velocity

p average electron drift path

k fraction of path to thickness

- we have:

$$v_d = \mu E$$

$$p = v_d \tau$$

$$k = p/d = \frac{\mu E \tau}{d} = \frac{\mu \tau V}{d^2}$$

CCE is related to k by Hecht equation:

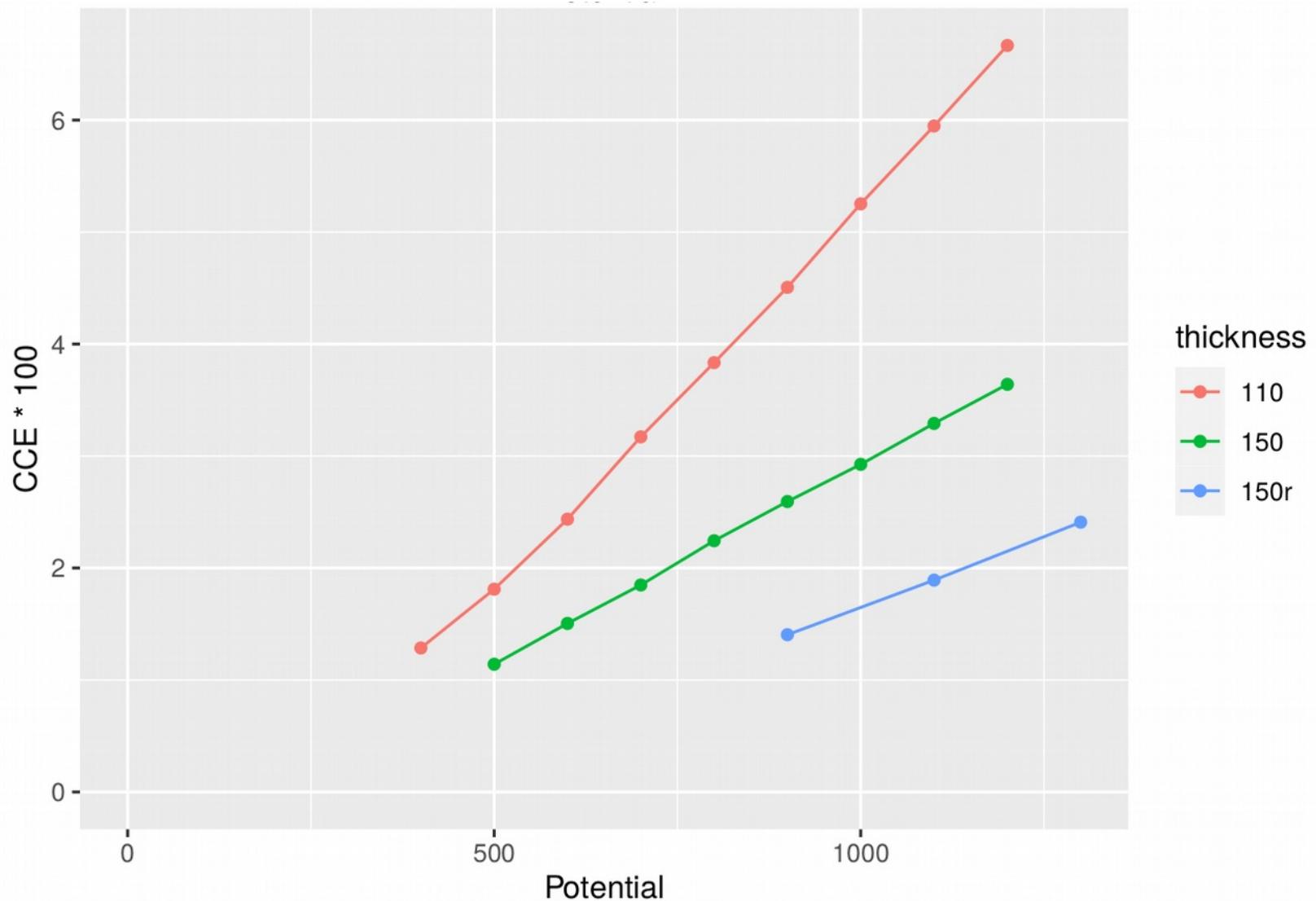
$$CCE = k(1 - \exp(-1/k))$$

and we can fit the data as a function of V for determining $\mu \tau$

Results

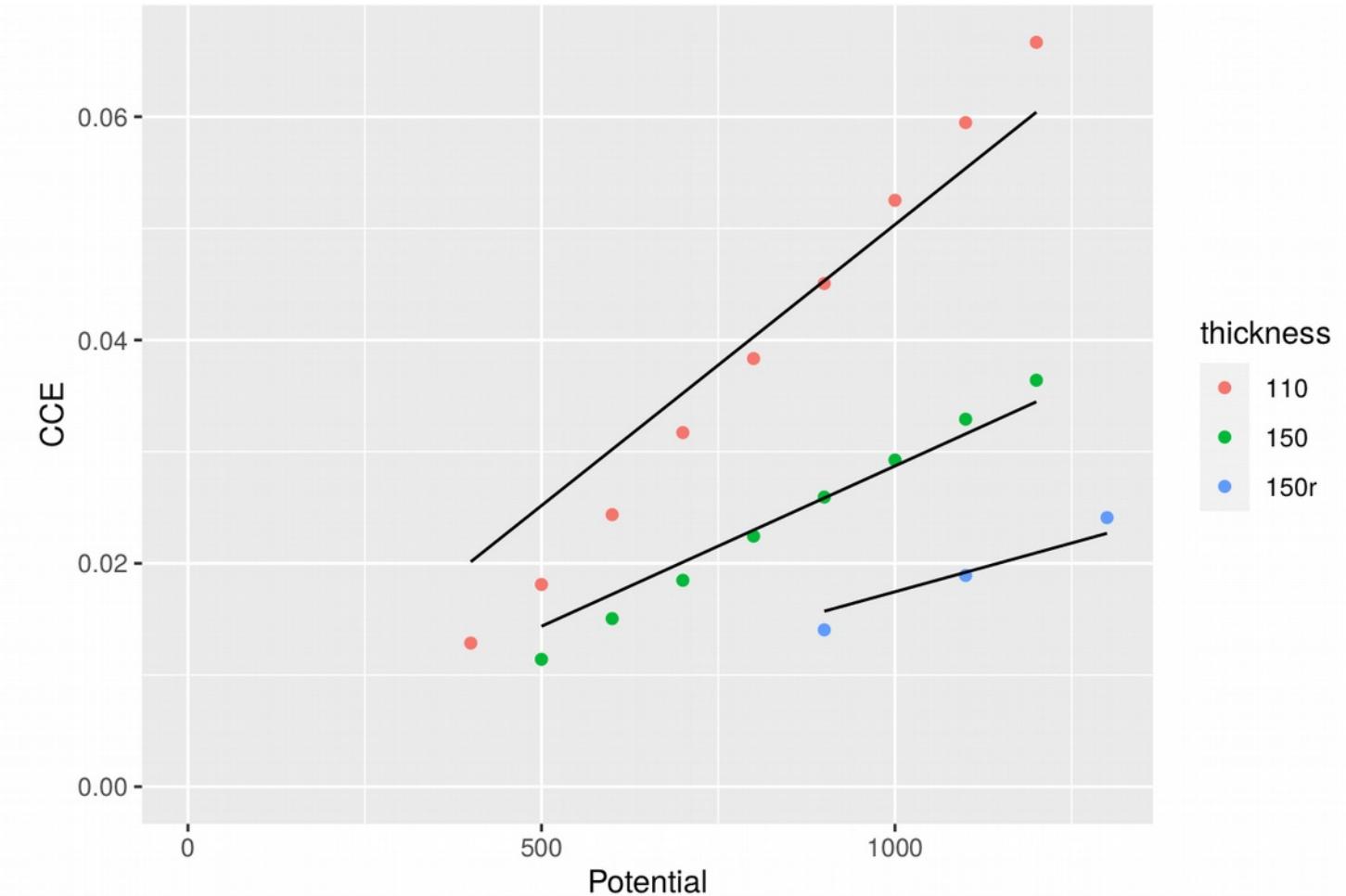
thickness um	Potential V	Signal_low mV	Signal_high mV	Signal fC	CCE
110	400	-94.3	-93.5	0.38	1.29%
110	500	-133.5	-131.0	0.54	1.81%
110	600	-179.5	-176.3	0.73	2.44%
110	700	-233.3	-229.9	0.95	3.17%
110	800	-282.3	-277.7	1.14	3.83%
110	900	-332.4	-325.8	1.34	4.51%
110	1000	-388.5	-378.6	1.57	5.25%
110	1100	-440.0	-428.7	1.77	5.95%
110	1200	-489.8	-483.9	1.99	6.67%
150	500	-83.8	-82.8	0.34	1.14%
150	600	-110.8	-109.0	0.45	1.50%
150	700	-136.1	-133.9	0.55	1.85%
150	800	-165.2	-162.5	0.67	2.24%
150	900	-190.8	-188.0	0.77	2.59%
150	1000	-215.6	-211.7	0.87	2.93%
150	1100	-243.4	-237.3	0.98	3.29%
150	1200	-268.5	-263.2	1.09	3.64%
150.0	900.0	101.3	103.8	0.42	1.40%
150.0	1,100.0	137.2	139.1	0.56	1.89%
150.0	1,300.0	175.0	176.9	0.72	2.41% ⁶

Results: CCE



Results: mu x tau

- Points do not align on a straight line from the origin as foreseen by the Hecht equation
- $\mu \tau = 6.09 \times 10^{-9} \text{ cm}^2/\text{V}$
for 110 um sapphire
- $\mu \tau = 6.46 \times 10^{-9} \text{ cm}^2/\text{V}$
for 150 um sapphire
- $\mu \tau = 3.93 \times 10^{-9} \text{ cm}^2/\text{V}$
for 150 um sapphire
reversed voltage



Results: mu x tau

- Fitting for:

$$CCE = CCE_0 + k(1 - \exp(-1/k))$$

- one obtains:

$$\mu\tau = 8.25 \times 10^{-9} \text{ cm}^2/\text{V}$$

$$CCE_0 = -1.57 \%$$

for 110 um sapphire

$$\mu\tau = 8.04 \times 10^{-9} \text{ cm}^2/\text{V}$$

$$CCE_0 = -0.64 \%$$

for 150 um sapphire

$$\mu\tau = 5.65 \times 10^{-9} \text{ cm}^2/\text{V}$$

$$CCE_0 = -0.86 \%$$

for 150 um sapphire - reversed bias

- with $\mu \sim 600 \text{ cm}^2/\text{Vs}$:

$$\tau \sim 13 \text{ ps}$$

